

10/796,656

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Substitute for form 1449/PTO (Revised 07/2005)  <b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b> (Use as many sheets as necessary)		<b>Complete if Known</b>			
		Application Number	10/796,656		
		Filing Date	March 9, 2004		
		First Named Inventor	Hamada, et al.		
		Group Art Unit	2012 2813		
Examiner Name	Smoot, Stephen				
Sheet	4	of	4	Attorney Docket Number	035576/275601

DC-For Ref -3

## FOREIGN PATENT DOCUMENTS

Examiner Initials	Cite No.	Foreign Patent Document Country Code - Number Kind Code (if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear	English Language Translation Attached
S.W.S.	54	JP 2002-038090 A	02-06-2002	JSR Corp.		Abstract only
S.W.S.	55	WO 00/12640	03-09-2000 2003	Catalysts & Chemicals Industries Co., Ltd.		Abstract only
S.W.S.	56	WO 03/088344	10-23-2003	Honeywell International, Inc.		

IDC-Other Ref -2

## OTHER DOCUMENTS

Examiner Initials*	Cite No.	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and-or country where published.	English Language Translation Attached
S.W.S.	57	BURKETT ET AL., "Synthesis Of Hybrid Inorganic-Organic Mesoporous Silica By Co-Condensation Of Siloxane And Organosiloxane Precursors," <u>J. Chem. Soc. Chem. Commun.</u> , 1996, 1367-1368.	
S.W.S.	58	INAGAKI ET AL., "Synthesis Of Highly Ordered Mesoporous Materials From A Layered Polysilicate", <u>J. Chem. Soc. Chem. Commun.</u> , 1993, pp. 680-682.	

Examiner Signature	Stephen W. Smoot	Date Considered	March 16, 2006
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\*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.